

Symposium (Oral) | Symposium (technical) | Etching Technology for Nitride Semiconductors: recent progress in high-controllable and low-damaging process

[20p-E301-1~9]Etching Technology for Nitride Semiconductors: recent progress in high-controllable and low- damaging process

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Fri. Sep 20, 2019 1:30 PM - 5:35 PM E301 (E301)

△ : Presentation by Applicant for JSAP Young Scientists Presentation Award

▲ : English Presentation

▼ : Both of Above

No Mark : None of Above

1:30 PM - 1:35 PM

[20p-E301-1]Introductory Talk

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Keywords:GaN etching